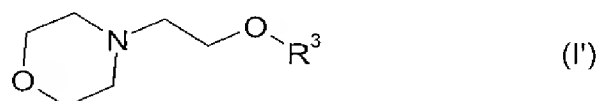


The listing of claims will replace all prior versions, and listings, of claims in the application:

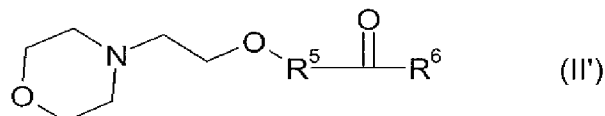
Listing of Claims:

1. (Previously Presented) An amine compound of the following formula (I'):



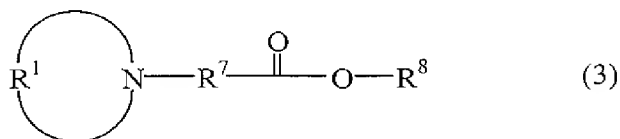
wherein R^3 is hydrogen or a straight, branched or cyclic alkyl which optionally contains one or more hydroxy groups, ether groups, carbonyl groups, ester groups, lactone rings or carbonate groups.

2. (Previously Presented) An amine compound of the following formula (II'):



wherein R^5 is a single bond or a straight, branched or cyclic alkylene group of 1 to 20 carbon atoms, and R^6 is hydrogen or a straight, branched or cyclic alkyl or alkoxy group of 1 to 20 carbon atoms which optionally contains one or more hydroxy groups, ether groups, carbonyl groups, ester groups, lactone rings or carbonate groups.

3. (Previously Presented) An amine compound of the following formula (3):

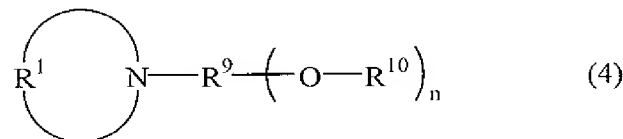
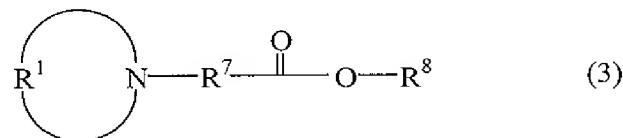
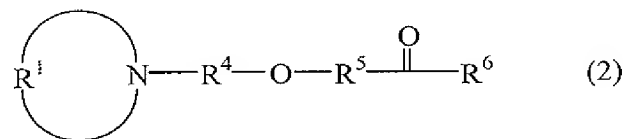
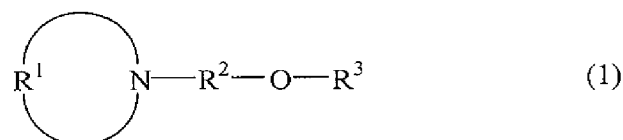


wherein R^1 is a straight or branched alkylene group of 2 to 20 carbon atoms which optionally

contains at least one carbonyl, ether, ester or sulfide group, R^7 is a straight or branched alkylene group of 1 to 10 carbon atoms, R^8 is a straight, branched or cyclic alkyl group of 1 to 20 carbon atoms which optionally contains one or more hydroxy groups, ether groups, carbonyl groups, ester groups, lactone rings or carbonate groups, and R^7 and R^8 , taken together, optionally form a ring with the COO.

4. (Canceled)

5. (Previously Presented) A resist composition comprising at least one amine compound of the following formulae (1) to (4):



wherein R^1 is a straight or branched alkylene group of 2 to 20 carbon atoms which optionally contains at least one carbonyl, ether, ester or sulfide group,

R^2 , R^4 and R^7 each are a straight or branched alkylene group of 1 to 10 carbon atoms,

R^3 and R^6 are, each independently, hydrogen or a straight, branched or cyclic alkyl or alkoxy group of 1 to 20 carbon atoms which optionally contains one or more hydroxy groups, ether groups, carbonyl groups, ester groups, lactone rings or carbonate groups,

R^5 is a single bond or a straight, branched or cyclic alkylene group of 1 to 20 carbon atoms,

R^8 is a straight, branched or cyclic alkyl group of 1 to 20 carbon atoms which optionally contains one or more hydroxy groups, ether groups, carbonyl groups, ester groups, lactone rings or carbonate groups,

R^2 and R^3 , taken together, optionally form a ring with the oxygen atom,

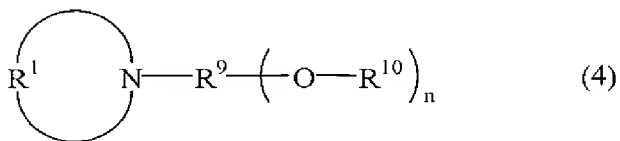
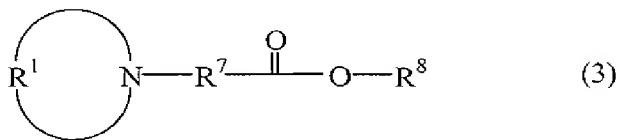
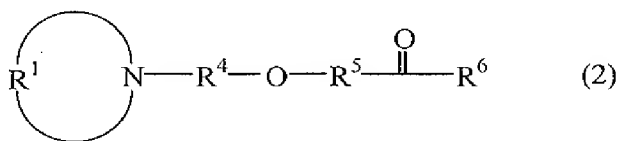
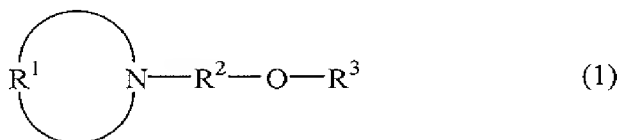
R^7 and R^8 , taken together, optionally form a ring with the COO,

R^9 is a (n+1)-valent organic group of 2 to 10 carbon atoms,

R^{10} which is the same or different is hydrogen or a straight, branched or cyclic alkyl or alkoxy group of 1 to 20 carbon atoms which optionally contains one or more hydroxy groups, ether groups, carbonyl groups, ester groups, lactone rings or carbonate groups, and

n is equal to 2, 3 or 4.

6. (Previously Presented) A positive resist composition comprising
(A) at least one amine compound of the following formulae (1) to (4):



wherein R¹ is a straight or branched alkylene group of 2 to 20 carbon atoms which optionally contains at least one carbonyl, ether, ester or sulfide group,

R², R⁴ and R⁷ each are a straight or branched alkylene group of 1 to 10 carbon atoms,

R³ and R⁶ are, each independently, hydrogen or a straight, branched or cyclic alkyl or alkoxy group of 1 to 20 carbon atoms which optionally contains one or more hydroxy groups, ether groups, carbonyl groups, ester groups, lactone rings or carbonate groups,

R⁵ is a single bond or a straight, branched or cyclic alkylene group of 1 to 20 carbon atoms,

R⁸ is a straight, branched or cyclic alkyl group of 1 to 20 carbon atoms which optionally contains one or more hydroxy groups, ether groups, carbonyl groups, ester groups, lactone rings or carbonate groups,

R² and R³, taken together, optionally form a ring with the oxygen atom,

R⁷ and R⁸, taken together, optionally form a ring with the COO,

R⁹ is a (n+1)-valent organic group of 2 to 10 carbon atoms,

R¹⁰ which is the same or different is hydrogen or a straight, branched or cyclic alkyl or alkoxy group of 1 to 20 carbon atoms which optionally contains one or more hydroxy groups, ether groups, carbonyl groups, ester groups, lactone rings or carbonate groups, and

n is equal to 2, 3 or 4,

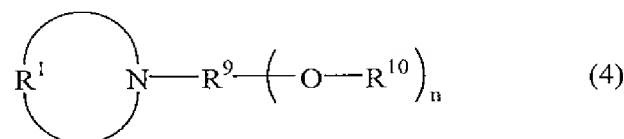
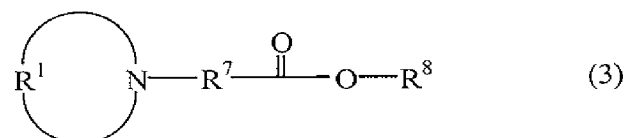
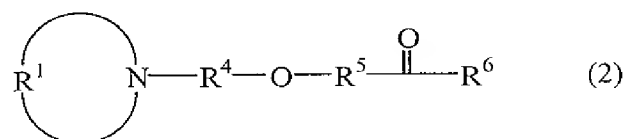
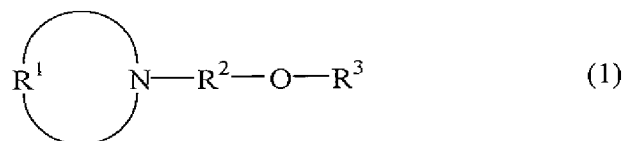
(B) an organic solvent,

(C) a base resin having an acidic functional group protected with an acid labile group, which is normally alkali insoluble or substantially alkali insoluble, but becomes alkali soluble upon elimination of the acid labile group, and

(D) a photoacid generator.

7. (Original) The positive resist composition of claim 6 further comprising (E) a dissolution inhibitor.

8. (Currently Amended) A negative resist composition comprising
 (A) \geq at least one amine compound of the following formulae (1) to (4):



wherein R^1 is a straight or branched alkylene group of 2 to 20 carbon atoms which optionally contains at least one carbonyl, ether, ester or sulfide group,

R^2 , R^4 and R^7 each are a straight or branched alkylene group of 1 to 10 carbon atoms,

R^3 and R^6 are, each independently, hydrogen or a straight, branched or cyclic alkyl or alkoxy group of 1 to 20 carbon atoms which optionally contains one or more hydroxy groups, ether groups, carbonyl groups, ester groups, lactone rings or carbonate groups,

R^5 is a single bond or a straight, branched or cyclic alkylene group of 1 to 20 carbon atoms,

R^8 is a straight, branched or cyclic alkyl group of 1 to 20 carbon atoms which optionally contains one or more hydroxy groups, ether groups, carbonyl groups, ester groups, lactone rings or carbonate groups,

R^2 and R^3 , taken together, optionally form a ring with the oxygen atom,

R^7 and R^8 , taken together, optionally form a ring with the COO,

R^9 is a (n+1)-valent organic group of 2 to 10 carbon atoms,

R^{10} which is the same or different is hydrogen or a straight, branched or cyclic alkyl or alkoxy group of 1 to 20 carbon atoms which optionally contains one or more hydroxy groups, ether groups, carbonyl groups, ester groups, lactone rings or carbonate groups, and

n is equal to 2, 3 or 4,

(B) an organic solvent,

(C') a base resin which is normally alkali-soluble, but becomes substantially alkali insoluble when crosslinked with a crosslinker,

(D) a photoacid generator, and

(F) the crosslinker capable of crosslinking under the action of acid.

9. (Previously Presented) A process for forming a resist pattern comprising the steps of:

applying the resist composition of claim 5 onto a substrate to form a coating,

heat treating the coating and then exposing it to high-energy radiation having a wavelength of less than 300 nm or electron beams through a photo mask, and

optionally heat treating the exposed coating and developing it with a developer.

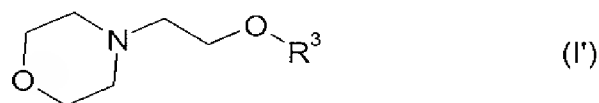
10. (Previously Presented) A process for forming a resist pattern comprising the steps of:

applying the resist composition of claim 6 onto a substrate to form a coating,

heat treating the coating and then exposing it to high-energy radiation having a wavelength of less than 300 nm or electron beams through a photo mask, and

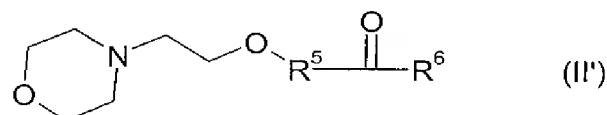
optionally heat treating the exposed coating and developing it with a developer.

11. (Previously Presented) A resist composition according to claim 5, comprising an amine compound of the following formula (I'):



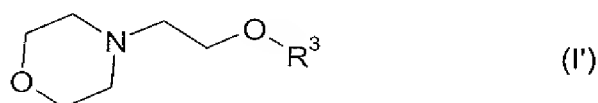
wherein R^3 is hydrogen or a straight, branched or cyclic alkyl which optionally contains one or more hydroxy groups, ether groups, carbonyl groups, ester groups, lactone rings or carbonate groups.

12. (Previously Presented) A resist composition according to claim 5, comprising an amine compound of the following formula (II'):



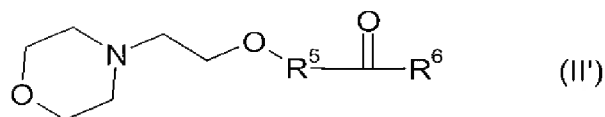
wherein R^5 is a single bond or a straight, branched or cyclic alkylene group of 1 to 20 carbon atoms, and R^6 is hydrogen or a straight, branched or cyclic alkyl or alkoxy group of 1 to 20 carbon atoms which optionally contains one or more hydroxy groups, ether groups, carbonyl groups, ester groups, lactone rings or carbonate groups.

13. (Previously Presented) A positive resist composition according to claim 6, comprising an amine compound of the following formula (I'):



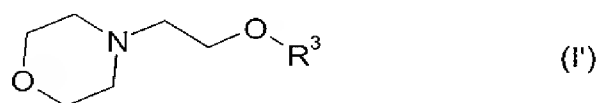
wherein R^3 is hydrogen or a straight, branched or cyclic alkyl which optionally contains one or more hydroxy groups, ether groups, carbonyl groups, ester groups, lactone rings or carbonate groups.

14. (Previously Presented) A positive resist composition according to claim 6, comprising an amine compound of the following formula (II'):



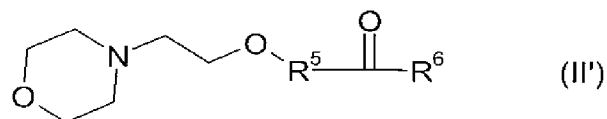
wherein R^5 is a single bond or a straight, branched or cyclic alkylene group of 1 to 20 carbon atoms, and R^6 is hydrogen or a straight, branched or cyclic alkyl or alkoxy group of 1 to 20 carbon atoms which optionally contains one or more hydroxy groups, ether groups, carbonyl groups, ester groups, lactone rings or carbonate groups.

15. (Previously Presented) A negative resist composition according to claim 8, comprising an amine compound of the following formula (I'):



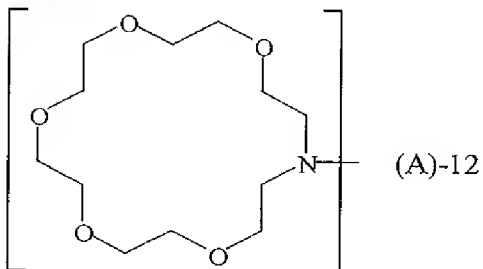
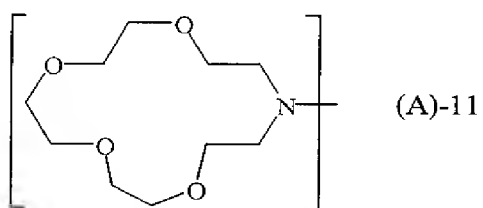
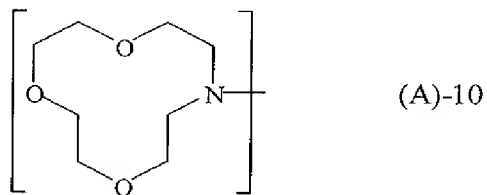
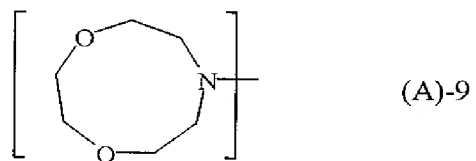
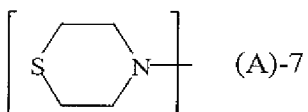
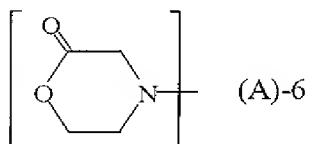
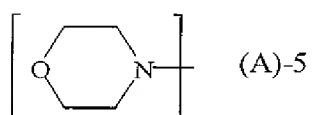
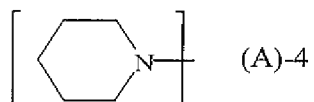
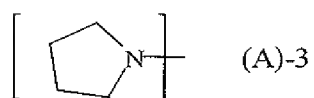
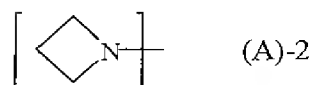
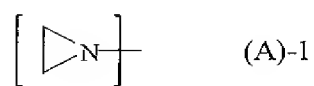
wherein R^3 is hydrogen or a straight, branched or cyclic alkyl which optionally contains one or more hydroxy groups, ether groups, carbonyl groups, ester groups, lactone rings or carbonate groups.

16. (Previously Presented) A negative resist composition according to claim 8, comprising an amine compound of the following formula (II'):



wherein R^5 is a single bond or a straight, branched or cyclic alkylene group of 1 to 20 carbon atoms, and R^6 is hydrogen or a straight, branched or cyclic alkyl or alkoxy group of 1 to 20 carbon atoms which optionally contains one or more hydroxy groups, ether groups, carbonyl groups, ester groups, lactone rings or carbonate groups.

17. (Previously Presented) A resist composition according to claim 5, comprising an amine compound of formula (3).
18. (Previously Presented) A positive resist composition according to claim 6, comprising an amine compound of formula (3).
19. (Previously Presented) A negative resist composition according to claim 8, comprising an amine compound of formula (3).
20. (Previously Presented) An amine compound according to claim 3, wherein the moiety (A) is a moiety of one of formulae (A)-1 to (A)-12,



or

21. (Previously Presented)
claim 20.

A resist composition comprising an amine compound of